

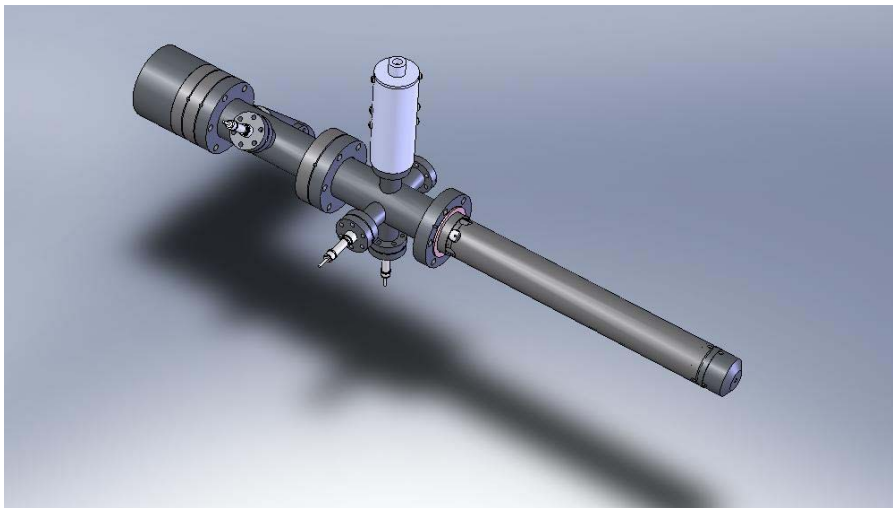
IQX 2013 & IPSU

High current density focused ion source for surface analysis



vsµanalysis

This new ion source is designed to satisfy a need for a robust , easy to use small area focused source ready for all tasks of the surface analysis from depth profiling to SIMS-TOF to sputter cleaning requirements.



Construction for a user in mind

High Current Density

- 5mA/cm²
- Spot size 100µm
- Differentially pumped
- Computer control of all parameters incl. spot size , raster area or focus distance
- Raster area to max 10 x 10 mm²
- Working distance 20 to 10mm

Construction Features

- Mounted on CF38
- Modular construction
- Easy to access
- Standardized connector for filament supply and Lens system

Power supply

- 5kV / 10mA psu
- Built in the latest resonance mode technology

VS MicroAnalysis

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